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Erratum

J. M. Fleischer, M. R. Latta, and M. E. Rabedeau, "Laser-Optical System of the IBM 3800 Printer," *IBM J. Res. Develop.* **21**, 479-483 (September 1977).

Page 479, Figure 1: Read "70.87 cells per cm" and "56.69 cells per cm" instead of "457 cells per cm" and "366 cells per cm," respectively.

Page 480, lines 8 and 10: Read "56.69 cells per cm" and "70.87 cells per cm" instead of "366 cells per cm" and "457 cells per cm," respectively.